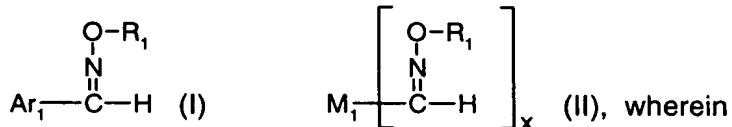


Abstract

Photosensitive compositions comprising

- (A) an alkali soluble compound;
- (B) at least one compound of formula I or II



R_1 inter alia is $\text{C}_4\text{-C}_9$ cycloalkanoyl, $\text{C}_3\text{-C}_{12}$ alkenoyl, or benzoyl which is unsubstituted or substituted; Ar_1 is either $\text{C}_6\text{-C}_{20}$ aryl or $\text{C}_6\text{-C}_{20}$ aryloyl each of which is unsubstituted or substituted; x is 2 or 3; M_1 when x is 2, inter alia is a group phenylene or naphthylene, each of which optionally is substituted i.a. by OR_3 , SR_4 or NR_5R_6 ; or M_1 , when x is 3, is a trivalent group, optionally substituted; R_3 is for example hydrogen or $\text{C}_1\text{-C}_{12}$ alkyl; $\text{C}_2\text{-C}_6$ alkyl which is for example substituted by -OH, -SH, -CN, $\text{C}_3\text{-C}_6$ alkenoxy, or - $\text{OCH}_2\text{CH}_2\text{CN}$; R_4 is for example hydrogen, $\text{C}_1\text{-C}_{12}$ alkyl, $\text{C}_3\text{-C}_{12}$ alkenyl, cyclohexyl, or phenyl which is unsubstituted or substituted; R_5 and R_6 independently of each other inter alia are hydrogen, $\text{C}_1\text{-C}_{12}$ alkyl, $\text{C}_2\text{-C}_4$ hydroxyalkyl, $\text{C}_2\text{-C}_{10}$ alkoxyalkyl, $\text{C}_3\text{-C}_5$ alkenyl, $\text{C}_3\text{-C}_8$ cycloalkyl, phenyl- $\text{C}_1\text{-C}_3$ alkyl, $\text{C}_1\text{-C}_4$ alkanoyl, $\text{C}_3\text{-C}_6$ alkenoyl, benzoyl or phenyl which is unsubstituted or substituted; and

(C) a photopolymerizable compound;

exhibit an unexpectedly good performance, in particular in photoresist technology.